

Substitute form 1449A/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Application Number	10/785,615
(use as many sheets as necessary)		Filing Date	02/24/2004
Sheet 1 of 2		First Named Inventor	Jeffry A. Kelber
		Group Art Unit	2841
		Examiner Name	Tuan T. Dinh
		Attorney Docket Number	5347-223



#### OTHER NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T
TD	1.	Bertel et al "The Adsorption of Bromine on Pt(111): Observation of an Irreversible Order-Disorder Transition" <u>Surface Science</u> 83:439-452 (1979)	
	2.	Bhaskar et al. "X-ray photoelectron spectroscopy and micro-Raman analysis of conductive RuO <sub>2</sub> Thin Films" <u>Journal of Applied Physics</u> , 89(5):2987-2992	
	3.	Böttcher et al. "Formation of subsurface oxygen at Ru(0001)" <u>The Journal of Chemical Physics</u> 110(6):3186-3195 (1999)	
	4.	Chan et al. "High-Pressure Oxidation of Ruthenium as Probed by Surface-Enhanced Raman and X-Ray Photoelectron Spectroscopies" <u>Journal of Catalysis</u> 172:336-345 (1997)	
	5.	Chyan et al. "Electrodeposition of Copper Thin Film on Ruthenium A Potential Diffusion Barrier for Cu Interconnects" <u>Journal of the Electrochemical Society</u> 150(5):C347-C350 (2003)	
	6.	Cumpson et al. "Elastic Scattering Corrections in AES and XPS. II. Estimating Attenuation Lengths and Conditions Required for their Valid Use in Overlayer/Substrate Experiments" <u>Surface and Interface Analysis</u> 25:430-446 (1997)	
	7.	DiCenzo et al. "XPS Studies of Adatom-Adatom Interactions: I/Ag(111) and I/Cu(111) <u>Surface Science</u> 121:411-420 (1982)	
	8.	Feibelman "Partial Dissociation of Water on Ru(0001)" <u>Science</u> 295(5552):99-102 (2002)	
	9.	Garwood, Jr. et al. "Surperlattices Formed by Interaction of Iodine, Water and Oxygen With the (111) Plane of an Fe-Cr-Ni Alloy fcc Single Crystal: Studies by Leed, Auger and Thermal Desorption Mass Spectroscopy" <u>Surface Science</u> 121:L524-L530 (1982)	
	10.	Grant et al. "A Study of Ru(0001) and Rh(111) Surfaces Using Leed and Auger Electron Spectroscopy" <u>Surface Science</u> 21:76-85 (1970)	
	11.	Hubbard "Electrochemistry at Well-Characterized Surfaces" <u>Chem. Rev</u> 88:633-656 (1988)	
	12.	Hwang et al. "Surfactant-Assisted Metallorganic CVD of (111)-Oriented Copper Films with Excellent Surface Smoothness" <u>Electrochemical and Solid-State Letters</u> 3(3):138-140 (2000)	
	13.	Kibler et al. "Initial stages of Pd deposition on Au(hkl) Part I: Pd on Au(111)" <u>Surface Science</u> 443:19-30 (1999)	
	14.	Kim et al. "Chemical state of ruthenium submonolayers on a Pt(111) electrode" <u>Surface Science</u> 474:L203-L212 (2001)	
	15.	Kiskinova et al. "Adsorption and Decomposition of H <sub>2</sub> O on a K-Covered Pt(111) Surface" <u>Surface Science</u> , 150:319-338 (1985)	
	16.	Kolb et al. "Scanning Tunneling Microscopy for Metal Deposition Studies" <u>Interface</u> 8(1):26-30 (1999)	
	17.	Kötz et al. "XPS Studies of Oxygen Evolution on Ru and RuO <sub>2</sub> Anodes" <u>Journal of the Electrochemical Society</u> , 130(4):825-829 (1983)	
	18.	Lin et al. "Combined Ultrahigh Vacuum/Electrochemistry Study of the Adsorption of Lead on Clean and Sulfur-Modified Nickel Surfaces in Aqueous Environments" <u>Langmuir</u> 14:3673-3681 (1998)	
	19.	Liu et al. "The Effects of an Iodine Surface Layer on Ru Reactivity in Air and during Cu Electrodeposition" <u>J. Electrochem. Soc.</u> , 152(2):G115-G121 (2005)	
	20.	Lu et al. "Adlattice Structure and Hydrophobicity of Pt(111) In Aqueous Potassium Iodide Solutions Influence of pH and Electrode Potential" <u>J. Electroanal. Chem.</u> 222:305-320 (1987)	
	21.	Lu et al. "In Situ Scanning Tunneling Microscopy of (Bi)sulfate, Oxygen, and Iodine Adlayers Chemisorbed on a Well-Defined Ru(001) Electrode Prepared in a Non-Ultrahigh-Vacuum Environment" <u>Langmuir</u> , 18:754-762 (2002)	
	22.	Madey et al. "Adsorption of Oxygen and Oxidation of CO on the Ruthenium (001) Surface" <u>Surface Science</u> 48:304-328 (1975)	
	23.	Madhavaram et al. "Oxidation Reactions over RuO <sub>2</sub> : A Comparative Study of the Reactivity of the (110) Single Crystal and Polycrystalline Surfaces" <u>Journal of Catalysis</u> 202:298-307 (2001)	
	24.	Martínez-Ruiz et al. "Underpotential deposition of Cu on iodine-modified Au(111): an in situ scanning tunneling microscopy study" <u>Surface Science</u> 476:139-151 (2001)	
	25.	Nakamura et al. "Monomer and tetramer water clusters adsorbed on Ru(0001)" <u>Chemical Physics Letters</u> 325:293-298 (2000)	
	26.	Oskam et al. "Electrochemical Deposition of Copper on n-Si/TiN" <u>Journal of the Electrochemical Society</u> 146(4):1436-1441 (1999)	
TD	27.	Quayum et al. "Mechanism for nucleation and growth of electrochemical palladium deposition on an Au(111) electrode" <u>Journal of Electroanalytical Chemistry</u> 520:128-132 (2002)	
TD	28.	Reuter et al. "Atomistic description of oxide formation on metal surfaces: the example of ruthenium" <u>Chemical Physics Letters</u> 352:311-317 (2002)	

Examiner Signature	/Tuan Dinh/	Date Considered	06/28/2006
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TD	29.	Seshadri et al. "Sulfur Catalyzed Electrochemical Oxidation of Copper: A Combined Ultrahigh Vacuum Electrochemistry Study" <u>Journal of the Electrochemical Society</u> 146(5):1762-1765 (1999)	
	30.	Seshadri et al. "The Promotion of the Anodic Dissolution of Polycrystalline Iron Surfaces by Adsorbed Sulfur: A UHV-Electrochemical Study" <u>Corrosion Science</u> 39(5):987-1000 (1997)	
	31.	Shen et al. "An ESCA study of the interaction of oxygen with the surface of ruthenium" <u>Applied Surface Science</u> 51:47-60 (1991)	
	32.	Sherwood "Curve fitting in surface analysis and the effect of background inclusion in the fitting process" <u>J. Vac. Sci. Technol A</u> 14(3):1424-1432	
	33.	Shi et al. "Reaction between H <sub>2</sub> O and Cs on the Ru(001) surface" <u>Surface Science</u> 317:45-57 (1994)	
	34.	Shue et al. "In Situ Scanning Tunneling Microscopy of Underpotential Deposition of Copper at Pt(100) Electrodes Coated with an Iodine Monolayer" <u>J. Phys. Chem. B</u> 105:5489-5496 (2001)	
	35.	Smith et al. "Evaluation of precursors for chemical vapor deposition of ruthenium" <u>Thin Solid Films</u> , 376:73-81 (2000)	
	36.	Stampfli et al. "Structure and Stability of a High-Coverage (X) Oxygen Phase on Ru(0001)" <u>Physical Review Letters</u> , 77(16):3371-3374 (1996)	
	37.	Stickney et al. "Electrodeposition of Copper on Platinum (111) Surfaces Pretreated With Iodine" <u>Journal of the Electrochemical Society</u> 131(2):260-267 (1984)	
	38.	Takahashi "Electroplating Copper Onto Resistive Barrier Films" <u>Journal of the Electrochemical Society</u> 147(4):1414-1417 (2000)	
	39.	Tanaka et al. "Kinetics of Oxidation Processes of Ruthenium Particles" <u>J. Am. Ceram. Soc.</u> 81(10):2513-2516 (1998)	
	40.	Tanuma et al. "Calculations of Electron Inelastic Mean Free Paths. V. Data for 14 Organic Compounds over the 50-2000 eV Range" <u>Surface and Interface Analysis</u> 21(3):165-176 (1994)	
↓	41.	Wang et al. "Seedless Electrodeposition of Cu on Unmodified Tungsten" <u>Electrochemical and Solid-State Letters</u> 5(9):C-82-C84 (2002)	
TD	42.	Wieckowski et al. "Preparation of Well-Defined Surfaces at Atmospheric Pressure: Studies by Electrochemistry and LEED of Pt(100) Pretreated With Iodine" <u>Inorg. Chem.</u> 23:565-569 (1984)	

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